

- Page 13, line 8, change "voltage-lowing" to --voltage-lowering--.
- Page 16, line 17, change "NOMOS" to --NMOS--.
- Page 20, line 5, change "a" to --the--;
- line 10, change "terminal." to --terminal).--;
- line 27, change "voltage-lowing" to --voltage-lowering--.
- Page 21, line 19, after "drain" (second occurrence) insert --of--;
- line 25, after "between" insert --resistors R1 and R2--.
- Page 30, after "buffer" insert --circuit--.
- Page 31, after "decoder" insert --60--.
- Page 32, line 3, delete "is";
- line 4, change "act" to --acts--.

**IN THE CLAIMS:**

Please amend the claims as follows:

*A. Sub B17*

1. (Amended) A semiconductor integrated circuit device comprising:

a semiconductor substrate on which a plurality of transistors including gate insulation films of different thicknesses are formed; and

an input/output terminal formed on the semiconductor substrate, wherein a transistor connected directly to the input/output terminal [being] is one of the transistors other than a transistor having the thinnest gate insulation film.

- Claim 2, line 4, before "a" insert --wherein--;
- line 5, change "being" to --is--.